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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

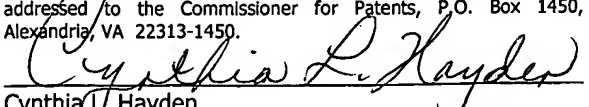
In re Applicant:	§	
Leonard C. Pipes et al.	§	Art Unit: 2812
	§	
Serial No.: 10/764,751	§	Examiner: Stanetta D. Isaac
	§	
Filed: January 26, 2004	§	Atty Docket: ITL.0851D1US
	§	P15016D
For: Implanting Ions in Shallow	§	
Trench Isolation Structures	§	Assignee: Intel Corporation

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Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

**REPLY TO FINAL REJECTION**

Sir:

In response to the final rejection mailed August 10, 2005, please amend the above-referenced patent application as follows:

Date of Deposit: August 26, 2005  
I hereby certify under 37 CFR 1.8(a) that this correspondence is being deposited with the United States Postal Service as **first class mail** with sufficient postage on the date indicated above and is addressed to the Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450.  
  
Cynthia L. Hayden